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APPLICANTS Kazuo Nishimoto, Tokyo, JAPAN; Tatsuaki Sakano, Tokyo, JAPAN; Akihiro Takemura, Tokyo, JAPAN; Masayuki Hattori, Tokyo, JAPAN; Nobuo Kawahashi, Tokyo, JAPAN; Naoto Miyashita, Yokohama-shi, JAPAN; Atsushi Shigeta, Fujisawa-shi, JAPAN; Yoshitaka Matsui, Yokohama-shi, JAPAN; Kazuhiko Ida, Yokohama-shi, JAPAN; ** CONTINUING DATA ***** <i>None MM</i> ** FOREIGN APPLICATIONS ***** JAPAN 2002-318643 10/31/2002 JAPAN 2003-056093 03/03/2003 <i>YES MM</i> IF REQUIRED, FOREIGN FILING LICENSE GRANTED ** 01/28/2004					
Foreign Priority claimed <input checked="" type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 (a-d) conditions met <input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance Verified and Acknowledged Examiner's Signature <i>MM</i> Initials <i>ll</i>		STATE OR COUNTRY JAPAN	SHEETS DRAWING 0	TOTAL CLAIMS 23	INDEPENDENT CLAIMS 3
ADDRESS 22850 OBLON, SPIVAK, MCCLELLAND, MAIER & NEUSTADT, P.C. 1940 DUKE STREET ALEXANDRIA, VA 22314					
TITLE Aqueous dispersion for chemical mechanical polishing, chemical mechanical polishing process, production process of semiconductor device and material for preparing an aqueous dispersion for chemical mechanical polishing					